Docket No.

210136US99

IN THE UNITED STATES PATENT RADEMARK OFFICE

IN RE APPLICATION OF:

Ravindranath DROOPAD, et al.

SERIAL NO:

09/901,109

GAU:

2815

FILED:

July 10, 2001

EXAMINER: BAUMEISTER

FOR:

STRUCTURE AND METHOD FOR FABRICATING SEMICONDUCTOR STRUCTURES AND DEVICES UTILIZING THE FORMATION OF A COMPLIANT SUBSTRATE COMPRISING AN OXYGEN-DOPED

COMPOUND SEMICONDUCTOR LAYER

INFORMATION DISCLOSURE STATEMENT UNDER 37 CFR 1.97

COMMISSIONER FOR PATENTS ALEXANDRIA, VIRGINIA 22313

Applicant(s) wish to disclose the following information.

REFERENCES

- The applicant(s) wish to make of record the references listed on the attached form PTO-1449. Copies of the listed references were submitted in application Serial No. 09/908,888 according to the attached copy of a Granted Petition. This application contains related subject matter.
- A check or credit card payment form is attached in the amount required under 37 CFR §1.17(p).

RELATED CASES

- ☐ Attached is a list of applicant's pending application(s) or issued patent(s) which may be related to the present application. A copy of the patent(s), together with a copy of the claims and drawings of the pending application(s) is attached along with PTO 1449.
- ☐ A check or credit card payment form is attached in the amount required under 37 CFR §1.17(p).

CERTIFICATION

- ☐ Each item of information contained in this information disclosure statement was first cited in a communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this statement.
- ☐ No item of information contained in this information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application or, to the knowledge of the undersigned, having made reasonable inquiry, was known to any individual designated in 37 CFR §1.56(c) more than three months prior to the filing of this statement.

DEPOSIT ACCOUNT

■ Please charge any additional fees for the papers being filed herewith and for which no check or credit card payment is enclosed herewith, or credit any overpayment to deposit account number 15-0030. A duplicate copy of this sheet is enclosed.

12/30/2003 AADOF01 00000089 09901109

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Respectfully submitted,

AK, McCLELLAND, NEUSTADT, P.C. MAIER &

Richard L. Treanor

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U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

ATTY DOCKET NO. 210136US99 09/901,109
APPLICANT

LIST OF REFERENCES CITED BY APPLICANT

Form PTO 1449 (Modified)

Ravindranath DROOPAD, et al.

FILING DATE GROUP

July 10, 2001 2815

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	XN	6,233,435 B1	05/15/01	WONG			
	хо	4,723,321	02/02/88	SALEH			
	XP	6,181,920 B1	01/30/01	DENT ET AL		L	
	XQ	6,415,140 B1	07/02/02	BENJAMIN ET AL			
	XR	5,760,740	06/02/98	BLODGETT		\perp	
	xs	5,238,877	08/24/93	RUSSELL			
	хт	4,876,218	10/24/89	PESSA ET AL			
	ΧU	6,232,242 B1	05/15/01	HATA ET AL			
	ΧV	4,378,259	03/29/83	HASEGAWA ET AL			
	xw	6,278,541 B1	08/21/01	BAKER			
	XY	4,298,247	11/03/81	MICHELET ET AL			
	XZ	4,174,504	11/13/79	CHENAUSKY ET AL			
	YA	3,758,199	09/11/73	THAXTER		<u> </u>	
	YB	6,362,558 B1	03/26/02	FUKUI			
	YC	6,140,746	10/31/00	MIYASHITA ET AL		<u> </u>	
	YD	2002/0076878 A1	06/20/02	WASA ET AL			
-	YE	6,419,849 B1	07/16/02	QIU ET AL			
	YF	2002/0179000 A1	12/05/02	LEE ET AL			
	YG	6,341,851	01/29/02	TAKAYAMA ET AL		<u> </u>	
	YH	2001/0055820 A1	12/27/01	SAKURAI ET AL		<u> </u>	
	ΥI	6,204,525 B1	03/20/01	SAKURAI ET AL			
	YJ	5,985,404	11/16/99	YANO ET AL			
	YK	6,538,359 B1	03/25/03	HIRAKU ET AL			
	YL	6,498,358 B1	12/24/02	LACH ET AL			
	YM	5,387,811	02/07/95	SAIGOH			
	YN	5,523,602	06/04/96	HORIUCHI ET AL			
	YO	5,362,998	11/08/94	IWAMURA ET AL			
	YP	5,188,976	02/23/93	KUME ET AL			
Examiner					Date Co	onsidered	

*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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SERIAL NO. ATTY DOCKET NO. YUS, DEPARTMENT OF COMMERCE Form PTO 1449 (Modified) 09/901,109 210136US99 **APPLICANT** LIST OF REFERENCES CITED BY APPLICANT Ravindranath DROOPAD, et.al. **GROUP** FILING DATE 2815 July 10, 2001 **U.S. PATENT DOCUMENTS** SUB FILING DATE DOCUMENT **EXAMINER CLASS** NAME DATE IF APPROPRIATE CLASS NUMBER INITIAL 12/31/02 YU ET AL 6,501,121 B1 YQ YANO ET AL YR 5,919,515 07/06/99 YS 5,238,877 08/24/93 RUSSELL **DENNARD ET AL** YT 5,540,785 07/30/96 5,997,638 12/07/99 COPEL ET AL YU 09/18/01 WALLACE YV 6,291,866 11/15/94 COOPER, JR ET AL 5,365,477 YW 08/20/96 MORRIS ET AL YΧ 5,548,141 KIM 02/21/02 YY 2002/0021855 08/29/00 YΠ 6,110,840 ΥZ ZΑ 5,667,586 09/16/97 **EK ET AL** FRIEDERICH ET AL 05/17/94 5,313,058 ZB 05/24/94 **HUNT ET AL** ZC 5,315,128 **BAUM ET AL** 07/06/99 ZD 5,919,522 06/27/89 **OHYA ET AL** ZΕ 4,843,609 **KUWANO ET AL** 12/02/86 ZF 4,626,878 FOYT ET AL ZG 4,525,871 06/25/85 06/18/74 COLEMAN ZΗ 3,818,451 Z١ 6.059.895 05/09/00 CHU ET AL 05/08/84 KING ET AL ΖJ 4,447,116 02/08/00 BINKLEY ET AL ZK 6,022,671 05/19/98 SUZUKI ET AL ZL 5,754,714 GAN ET AL 02/25/03 ZΜ 6,524,651 B2 KADOTA ET AL ΖN 6,355,945 B1 03/12/03 TOHYAMA ET AL 5,642,371 06/24/97 ZO 6,445,724 B2 09/03/02 **ABELES** ZΡ 05/19/98 YANO ET AL ZQ 5,753,934 6,326,667 B1 12/04/01 SUGIYAMA ET AL ZR 04/18/00 MASUDA ZS 6,051,874 OLSON ET AL 11/24/92 ZT 5,166,761 **GAW ET AL** 11/12/96 ΖU 5,574,744 **Date Considered** Examiner

*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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FILING DATE

July 10, 2001

GROUP

2815

FOREIGN PATENT DOCUMENTS

		1		T		
	DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES NO		
CCA	5-238894	09/17/93	JAPAN W/ENGLISH ABSTRACT			
 ССВ	2 152 315	07/31/85	GREAT BRITAIN			
ccc	2001-196892	07/19/01	JAPAN W/ENGLISH ABSTRACT			
CCD	2000-278085	10/06/00	JAPAN (ENGLISH ABSTRACT)			
CCE	WO 03/012874	02/13/03	WIPO			
CCF	1 043 427	10/11/00	EUROPE			
CCG	1 069 605	01/17/01	EUROPE			
ССН	WO 02/099885	12/12/02	WIPO			
CCI	10-269842	10/09/98	JAPAN W/ENGLISH ABSTRACT			
CC1	59066183	04/14/84	JAPAN (ENGLISH ABSTRACT)			
ССК	03046384	02/27/91	JAPAN (ENGLISH ABSTRACT)			
CCL	WO 02/11254	02/07/02	WIPO			
ССМ	0 494 514	07/15/92	EUROPE			
 CCN	0 247 722	12/02/87	EUROPE			
cco	1 037 272	09/20/00	EUROPE			
CCP	59-073498	04/25/84	JAPAN (ENGLISH ABSTRACT)			
CCQ	60-161635	08/23/85	JAPAN W/ENGLISH ABSTRACT			
CCR	59-044004	03/12/84	JAPAN W/ENGLISH ABSTRACT			
ccs	0 392 714	10/17/90	EUROPE			
 ССТ						
ccu					<u> </u>	
ccv						
ccw						
 CCX						
 CCY						
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Form PTO 1449	U.S. DEPARTMENT OF COMMERCE	ATTY DOCKET NO.	SERIAL NO.			
(Modified)	PATENT AND TRADEMARK OFFICE	210136US99	09/901,109			
		APPLICANT				
LIST OF REFE	RENCES CITED BY APPLICANT	Ravindranath DROOPAD, et al.				
		FILING DATE	GROUP			
•		July 10, 2001	2815			
	•	Including Author, Title, Date, Pertinent				
LLAA	Peter Weiss; "Speed demon gets hooked on silicon"; Science News Online; Sept. 15, 2001; pp. 1-3					
LLAE	"Motorola Develops New Super-Fast Chip"; USA Today; Sept. 4, 2001					
LLAC	Lori Valigra; "Motorola Lays GaAs on Si Wafer"; AsiaBizTech; Nov. 2001pp. 1-3					
LLAD	"Holy Grail! Motorola Claims High-Yield GaAs Breakthrough"; Micromagazine.com (no date available); pp. 1-3					
LLAE	Jong-Gul YOON; "Growth of Ferroelectric LiNbO3 Thin Film on MgO-Buffered Si by the Sol-Gel Method"; Journal of the Korean Physical Society (Proc. Suppl.); Vol. 29, Nov. 1996; pp. S648-S651					
LLAF	V. Bornand et al.; "Deposition of LiTaO3 thin films by pyrosol process"; Thin Solid Films 304 (1997); pp.239-244					
LLAG	R. Droopad et al.; "Development of high dielectric constant epitaxial oxides on silicon by molecular beam epitaxy"; Materials Science and Engineering B87 (2001); pp.292-296					
LLAH	A.K. Sharma et al.; "Integration of Pb(Zr0.52Ti0.48)O3 epilayers with Si by domain epitaxy"; Applied Physics Letters, Vol. 76, No. 11; March 13, 2000; pp. 1458-1460					
LLAI	Dwight C. Streit et al; "High Reliability GaAs-AlGaAs HBT's by MBE with Be Base Doping and InGaAs Emitter Contacts"; 8179 leee Electron Device Letters; 12(1991) September, No. 9, New York, US					
LLAJ	C. Y. Hung et al; "Piezoelectrically induced stress tuning of electro-optic devices"; 320 Applied Physics Letters; 59(1991) 30 December, No. 27, New York, US					
LLAK	J. Piprek; "Heat Flow Analysis of Long-Wvelength VCSELs with Various DBR Materials"; University of Delaware, Materials Science, Newark, DE, 19716-3106; Oct. 31, 1994; pp. 286-287					
LLAL	P. Mackowiak et al.; "Some aspects of designing an efficient nitride VCSEL resonator"; J. Phys. D: Appl. Phys. 34(2001); pp. 954-958					
LLAN	M.R. Wilson et al.; GaAs-On-Si: A GaAs IC Manufacturer's Perspective"; GaAs IC Symposium, IEEE, 1988; pp. 243-246					
LLAN	Y. Kitano et al.; "Thin film crystal growth of BaZrO3 at low oxygen partial pressure"; Journal of Crystal Growth 243 (2002); pp. 164-169					
LLAC	M.E. Hawley; et al; "Microstructural Study of Colossal Magneto-Resistive Films As a Function of Growth Temperature, As Deposited and Annealed"; 401, 1996; pp. 531-536					
LLAP						
LLAG						
Examiner	-		Date Considered			
		t citation is in conformance with MPEP 60 n with next communication to applicant.	9; Draw line through citation if not in			